

Amendments to the Claims:

The following listing of claims will replace all prior versions, and listings, of claims in the application:

1-10. (Canceled)

11. (Currently Amended) A manufacturing method for exposure apparatuses which ~~exposes~~ expose a second object by an exposure beam via a first object and a projection system, comprising:

a first step of assembling a first main body frame of an exposure apparatus in a first manufacturing line;

a second step of assembling a second main body frame of an exposure apparatus in a second manufacturing line;

a third step of installing a first adjustment stage at a position where a stage which aligns the first object of the first main body frame is placed in the first manufacturing line, and assembling and adjusting an illumination system to be mounted on the first main body frame;

a fourth step of assembling and adjusting a stage system which aligns the first object and the second object using the second main body frame in the second manufacturing line; and

a fifth step of removing the first adjustment stage from the first main body frame in the first manufacturing line, mounting the projection system and the stage system removed from the second main body frame on the first main body frame to assemble the first exposure apparatus.

12. (Original) The manufacturing method for exposure apparatuses according to Claim 11, wherein the second exposure apparatus is assembled and adjusted using the second main body frame in the second manufacturing line after the fifth step.

13. (Previously Presented) The manufacturing method for exposure apparatuses, according to claim 11, wherein the fifth step further comprises:

a first sub-step for mounting the projection system on the first main body frame;

a second sub-step for mounting the second adjustment stage on the first main body frame at a position where the stage which aligns the second object is placed, in order to adjust the projection system;

a third sub-step for removing the first and second adjustment stages from the first main body frame; and

a fourth sub-step for mounting the stage system removed from the second main body frame on the first main body frame.

14. (Original) The manufacturing method for exposure apparatuses according to Claim 11, wherein the first adjustment stage further comprises a pin hole which is movable two-dimensionally and a photo-electric detector which detects the exposure beam which passes through the pin hole by an optical Fourier transform surface, and dispersion of coherence factors of the illumination system is measured by the adjustment stage.

15. (Currently Amended) The manufacturing method for exposure apparatuses according to Claim 11, wherein the exposure apparatus is a scanning type exposure apparatus which moves the first object and the second object in a predetermined scanning direction synchronously to execute exposure, the first adjustment stage comprises a pin hole which is movable in a non-scanning direction which crosses the scanning direction, and a photo-electric detector which detects the exposure beam which passes through ~~the~~this pin hole, and substantially two-dimensional illuminance unevenness of the illumination system is measured using the adjustment stage.

16. (Original) The manufacturing method for exposure apparatuses according to Claim 13, further comprising a step of assembling and adjusting the illumination system to be mounted on the second main body frame by mounting the removed first adjustment stage at a position where the stage which aligns the first object of the second main body frame is placed in the second manufacturing line after removing the stage system from the second main body frame in the second manufacturing line.

17. (Original) The manufacturing method for exposure apparatuses according to Claim 16, further comprising a step of mounting the removed second adjustment stage on the second main body frame at a position where the stage which positions the second object is placed in order to adjust the projection system in the second manufacturing line.

18. (Original) The manufacturing method for exposure apparatuses according to Claim 11, wherein the exposure apparatus is a scanning type exposure apparatus which moves the first object and the second object in a predetermined scanning direction synchronously to execute exposure, the first adjustment stage comprises a slit which can move in a non-scanning direction which crosses the scanning direction, and a photo-electric detector which detects the exposure beam which passes through this slit, and substantially

two-dimensional illuminance unevenness of the illumination system is measured using the adjustment stage.

19. (Original) The manufacturing method for exposure apparatuses according to Claim 11, wherein the stage system installed to the second main body frame is adjusted based on a positional relationship between the first main body frame and the first adjustment stage.

20. (Original) The manufacturing method for exposure apparatuses according to Claim 13, wherein the stage system installed to the second main body frame is adjusted based on a positional relationship between the first main body frame and the second adjustment stage.

21. (Original) The manufacturing method for exposure apparatuses according to Claim 20, wherein a partial illumination system at the first object side of the illumination system is slidably installed to the first main body frame, and the partial illumination system is retracted when the first adjustment stage is attached to/removed from the first main body frame and when the stage system is installed.

22-34. (Canceled)